

Supporting Information for

**Weak-Acids Enhance Halogen Activation on Atmospheric
Water's Surfaces**

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Figure S1 Surface excess versus concentration of hexanoic acid or octanoic acid at pH 2.3 reproduced from Lunkenheimer et al. Langmuir, **2003**, *19*, 6140.

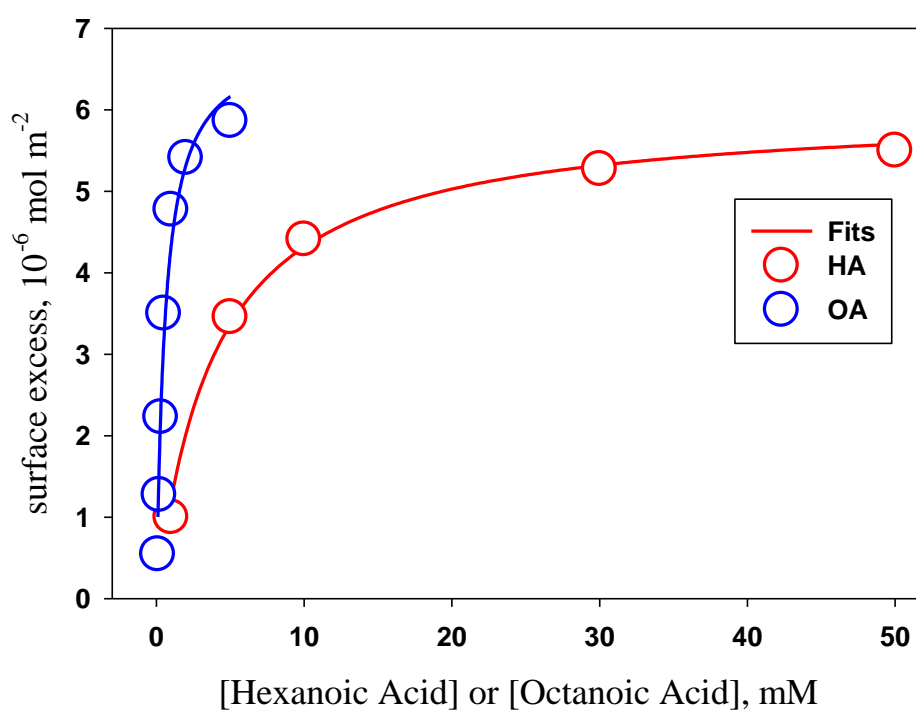


Fig. S1